

SUBSTRATE WITH THIN FILM, AND SEMICONDUCTOR SUBSTRATE

Abstract

A substrate with a thin film, including
the thin film including a Si-R¹ group of a compound represented by Formula (1), and
the substrate including the thin film including the Si-R¹ group, the thin film being
disposed on a surface of the substrate,



where in Formula (1), R¹ represents a monovalent organic group that bonds to Si; R² represents a monovalent organic group that bonds to Si; R³ represents an alkoxy group, an acyloxy group, or a halogen atom that bonds to Si; n represents an integer from 0 to 2; when n is 2, R² may be the same or different; when n is 0 or 1, R³ may be the same or different; and when n is 1, R¹ and R² may bond together to form a ring structure.

<Fig. 1>